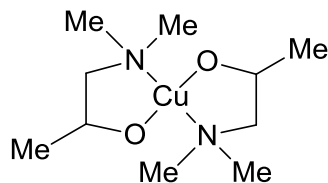


Catalog # 29-7120

Bis(dimethylamino-2-propoxy)copper(II), min. 97% Cu(dmap)₂

Technical Note:

1. ALD/CVD precursor for the preparation of Cu, Cu₂O, or Cu₂S films for electronic applications at temperatures ranging from 135 to 170°C. The T_{Subl} = 90°C/0.05 Torr and has a decomposition temperature of 185-188°C.

References:

1. *Chem. Mater.*, **2011**, 23, 4411
2. *Chem. Mater.*, **2014**, 26, 3731
3. *J. Phys. Chem. C* **2015**, 119, 9375
4. *Dalton Trans.*, **2015**, 44, 10188
5. *Chem. Mater.* **2016**, 28, 6282
6. *Dalton Trans.*, **2017**, 46, 5790
7. *Chem. Mater.* **2017**, 29, 6502